KMPR 1005 — run sheet

Kayaku Microchem (MicroChem)

nanyte.com/photoresists/kmpr-1005 · last updated 2026-07-26

Thickness: 5.1–9.7 µm

Softbake: 100 °C · 5 min · hotplate

Exposure dose — dose by film thickness

Film thickness	Dose
5–11 µm	235–335 mJ/cm²

Post-exposure bake: 100 °C · 2 min

Develop: Developer 2.38% TMAH (0.26N) aqueous alkaline developer (primary); SU-8 Developer (solvent-based) is also usable as an alternative · Dilution 2.38% TMAH (0.26N), used at this standard concentration (not diluted from a stock in the document) · Time 3 min · Rinse DI water, ~20 s spray rinse, then filtered air/N2 dry (TMAH path). If the optional SU-8-developer alternative is used instead, rinse is ~10 s fresh developer spray then ~10 s IPA spray, per the SU-8-developer note. · Method immersion